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The interplay between optical properties and structure of coatings for GWD

Spectroscopic Ellipsometry of coatings

ADCOAT: first results

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EINS



A long travel ... from cosmology ... to nanophysics









500pA,8KX, 2-3

2 1.00

E-Beam Spot Mag EWD Tit Det



The coating affair: issues



- Very ultra low optical absorptions
 ~ ppm
- Ultra High Uniformity "bulk"& surface

Very ultra low mechanical Losses main source of thermal noise

@ 100-300 Hz



Ta₂O₅:Ti still the best option for the high index material in $\lambda/4$ multilayers

Mechanical Losses: Main trends (@LMA)

- no significant dependence on thickness of Ta2O5:Ti sub-unit
- significant increase with the number of interfaces in multilayers
- Losses on multilayers larger than the sum of monolayer losses
- Losses for ALD films comparable to IBS films

"nano-bugs" at interfaces <u>&</u> film

Spectroscopic Ellipsometry of GWD coatings









Spectroscopic Ellipsometry (isotropic systems: Fresnel theory)





$$\begin{split} \rho &= t \, g \Psi e^{i\Delta} = \frac{R_{\rho}}{R_{s}} = \frac{r_{0,1}^{\rho} + r_{1,2}^{\rho} e^{-2i\beta}}{1 + r_{0,1}^{\rho} r_{1,2}^{\rho} e^{-2i\beta}} \cdot \frac{1 + r_{0,1}^{s} r_{1,2}^{s} e^{-2i\beta}}{r_{0,1}^{s} + r_{1,2}^{s} e^{-2i\beta}} \\ & \beta = 2\pi \frac{d}{\lambda} \sqrt{\tilde{N}_{1}^{2} - \tilde{N}_{0}^{2} \sin^{2} \Phi} \end{split}$$
$$\begin{split} \rho &= \rho(\tilde{N}_{0}, \tilde{N}_{1}, \tilde{N}_{2}, d, \lambda, \varphi) \end{split}$$

Comparison data/simulations: needs a model of the optical system If ambient and substrate properties are known with precision One needs (n,k) and d of the film $MSE = \frac{1}{2N-M} \sum_{i=1}^{N} \left[\left(\frac{\Psi_i^{\text{mod}} - \Psi_i^{\text{exp}}}{\sigma_{\Psi,i}^{\text{exp}}} \right)^2 + \left(\frac{\Delta_i^{\text{mod}} - \Delta_i^{\text{exp}}}{\sigma_{\Delta,i}^{\text{exp}}} \right)^2 \right] = \frac{1}{2N-M} \chi^2$





Transparency region: thickness and n No surface, no interface...





$$n = A + \frac{B}{\lambda^{2}} + \frac{C}{\lambda^{4}}$$
$$k = D \cdot e^{F(hv - G)}$$

thickness ~ **134 nm** n@1064nm = **2.057** k@1064nm < 10⁻³

> R. Flaminio et al. Class.Quantum Grav. **27** (2010) 084030

 $n@1064nm \sim 2.06$ Monolayer absorption ~ 1.2 ppm (i.e. k $\approx 2~10^{-7})$



Extending the wavelength range over the gap 0.75-5 eV (245-1700 nm)



Including defects

Amorphous oxides: Cody-Lorentz model - Urbach tail

[A. S. Ferlauto et al., Journal of Appliea Physics 92 (2002)]







Ta2O5/SiO2 (LMA)

Prato et al., Thin Solid Films 519 (2011) 2877

Including non-uniformity

The "simplest model" : Roughness layer + transition layer



...Non-ideal interface....

Spectroscopic Ellipsometry + PCI@1064nm

(Ta2O5/SiO2- CSIRO) Anghinolfi et al., JPhysD 46 (2013) 455301







Ta2O5/Void Graded EMA (Maxwell-Garnett)







Three models for absorption edge of amorphous semiconductors

						Anghinolfi et al., JPhysD 2013	
	Id.	$T_{\rm ann}$ (°C)	$\operatorname{CL}(E_g)$	$\mathrm{TL}\left(E_{\mathrm{g}}\right)$	TP (CL,TL,Psemi)	Thickness (nm)	Abs.@1064 nm(ppm)
40 nm	S 1	n/a	1 15	4.13	4.20 ± 0.1	38.2	0.9
	S2	450	4.18	4 17	4.24 ± 0.1	38.9	3.2
	S 3	550	4.16	4.16	4.24 ± 0.1	39.1	2.9
500 nm	S 4	300	4.13	4.13	4.19 ± 0.1	514.6	1.1
	S 5	400	4.13	4.13	4.19 ± 0.1	515.6	1.4
	S 6	500	4.13	4.13	4.19 ± 0.1	517.6	2.1
	S 7	600	4.15	4.13	4.19 ± 0.1	519.9	1.9



Ta2O5/SiO2- CSIRO











increase of NIR absorption losses (PCI at 1064 nm).







slight blue-shift of Eg (+ evident on the 40 nm thick coating) Improved stoichiometry Onset of (nano)-crystallization (to be checked e.g. With Raman)





Optical properties vs. Tann testify micro-structural modifications \rightarrow (nano-pores model)

pores may play a crucial role in the release of compressive strain induced by the densification @ deposition

pores (especially open ones) tend to reduce the effective refractive index of the coating. The relatively modest effects on n are consistent with a main population of closed pores

the increase in dīa205 and in the average pore density with increasing Tann, coupled to the reduction of n can be associated with the expansion of nano-cavities

future - extending the range in the UV → 190 nm - scatterometry (in-plane) - couple SE with high ex-situ sensititivity structural probes (Raman, XRD) and with TEM - study SiO2/Ta2O5/SiO2 system vs annealing - real time SE to monitor slow annealing







Debugging" Ta2O5:Ti

- better control of annealing process (T, t)
- unambiguous "decoding" of trends
- How and why "dopants" work?

Searching for "the best" glassy oxide mixture

"failed" sofar

Optimizing the design

- e.g. fine tuning of thickness of bilayer units [Villar et al., PRD 81 (2010) 122001]

Testing new materials and multilayers

e.g for low T operation (silica doped Hafnia)
nanolayered composites (Titania::Silica and Hafnia::Silica)

modelling (Effective Medium Theory)

mechanical losses
[Villar et al., LIGO- G1100 976]
optical properties
[Anghinolfi et al. JphysD, 2013]

Testing

- extensive trial-and-error

YZ

ADCOAT People









LSC



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Courtesy I. Pinto



ADCOAT Nanolayer composites Prototypes





Si/TiO₂(x3) SiO₂(x2) not annealed: 250 Si/TiO₂(x3) SiO₂(x2) not annealed 60° - 60° 35 - 65° 65° 70° 200 70 fit 150 30 d∆ [deg] Ψ [deg] 100 25 50 20 0 -50 15 400 800 1200 1600 400 800 1200 1600 Wavelenght [nm] Wavelenght [nm] Titania-Silica (5 units) on Si

First stage of analysis Cauchy layers + roughness layer Transparency range 600-1700 nm

Full details in S. Chao et al., LIGO-G1200849

As deposited

 $d_{(TiO_2)} = 27.30 (\pm 0.05)$ vs. 27.1 nominal $n_{@1064nm(TiO_2)} = 2.32$ $d_{(SiO_2)} = 20.15 (\pm 0.05)$ vs. 19.9 nominal $n_{@1064nm(SiO_2)} = 1.48$

Work in progress ... 19 units M. Magnozzi, M. Neri, I. Solano, S. Uttiya